

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method of manufacturing a mask comprising:
attaching to a ~~first-substrate~~frame having an opening a ~~second-substrate~~screen
plate having a plurality of penetrating holes arranged to form a mask pattern such that the
penetrating holes are positioned within the opening, the penetrating holes set to be
~~perpendicular~~perpendicularly to a connect holes formed in opposite surfaces of the
~~second-substrate~~screen plate;
forming a groove on at least one of a surface of the ~~first-substrate~~frame facing
the ~~second-substrate~~screen plate and a surface of the ~~second-substrate~~screen plate facing the
~~first-substrate~~frame; and
utilizing the groove to form a flow path between the ~~first and second~~
~~substrates~~frame and the screen plate.
2. (Original) The manufacturing method of the mask as defined in claim 1,
wherein at least part of the groove is formed around the opening.
3. (Currently Amended) The manufacturing method of the mask as defined in
claim 1,
wherein the ~~first and second-substrate~~frame and the screen plate are joined by
anode coupling.
4. (Currently Amended) The manufacturing method of the mask as defined in
claim 2,
wherein the ~~first and second-substrate~~frame and the screen plate are joined by
anode coupling.

5. (Currently Amended) The manufacturing method of the mask as defined in claim 1, wherein the steps of forming the ~~second substrate~~screen plate includes:

forming the penetrating holes in a silicon wafer; and

cutting the silicon wafer into a shape corresponding to the ~~second substrate~~screen plate.

6. (Currently Amended) The manufacturing method of the mask as defined in claim 1, further comprising:

forming a magnetic film over the ~~second substrate~~screen plate.

7. (Currently Amended) The manufacturing method of the mask as defined in claim 1, wherein:

a plurality of the ~~second substrate~~screen plates are attached to the ~~first substrate~~frame;

the ~~first substrate~~frame has a plurality of the openings; and

each of the ~~second substrate~~screen plates is attached to corresponding one of the openings.

8. (Currently Amended) The manufacturing method of the mask as defined in claim 7, further comprising:

polishing surfaces of the ~~second substrate~~screen plates attached to the ~~first substrate~~frame to have a uniform height.

9. (Currently Amended) A mask comprising:

a ~~first substrate~~frame having an opening; and

a ~~second substrate~~screen plate attached to the ~~first substrate~~frame and having a plurality of penetrating holes arranged to form a mask pattern, the penetrating holes set to be ~~perpendicular~~perpendicularly to a connect holes formed in opposite surfaces of the ~~second substrate~~screen plate, wherein:

the ~~second-substrate~~screen plate is attached to the ~~first-substrate~~frame such that the penetrating holes are positioned within the opening;

a groove is formed on at least one of a surface of the ~~first-substrate~~frame facing the ~~second-substrate~~screen plate and a surface of the ~~second-substrate~~screen plate facing the ~~first-substrate~~frame; and

the groove is utilized to form a flow path between the ~~first-and-second~~
~~substrates~~frame and the screen plate.

10. (Original) The mask as defined in claim 9, wherein at least part of the groove is formed around the opening.

11. (Currently Amended) The mask as defined in claim 9, wherein the ~~first-and-second-substrates~~frame and the screen plate are joined by anode coupling.

12. (Currently Amended) The mask as defined in claim 10, wherein the ~~first-and-second-substrates~~frame and the screen plate are joined by anode coupling.

13. (Currently Amended) The mask as defined in claim 9, wherein a magnetic film is formed over the ~~second-substrate~~screen plate.

14. (Currently Amended) The mask as defined in claim 9, wherein:
a plurality of the openings are formed in the ~~first-substrate~~frame;
a plurality of the ~~second-substrates~~screen plates are attached to the ~~first~~
~~substrate~~frame; and
each of the ~~second-substrates~~screen plates is attached to corresponding one of the openings.

15. (Currently Amended) The mask as defined in claim 14, wherein surfaces of the ~~second-substrates~~screen plates attached to the ~~first-substrate~~frame are polished to have a uniform height.

16. (Original) A method of manufacturing an electro-luminescence device comprising:
forming a film of a light emitting material using the mask as defined in claim 9; and
cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

17. (Original) A method of manufacturing an electro-luminescence device comprising:
forming a film of a light emitting material using the mask as defined in claim 10; and
cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

18. (Original) A method of manufacturing an electro-luminescence device comprising:
forming a film of a light emitting material using the mask as defined in claim 11; and
cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

19. (Original) A method of manufacturing an electro-luminescence device comprising:
forming a film of a light emitting material using the mask as defined in claim 12; and
cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

20. (Original) An electro-luminescence device manufactured by the method as defined in claim 16.

21. (Original) An electronic instrument having the electro-luminescence device as defined in claim 20.

22. (Currently Amended) A method of manufacturing a mask comprising:
attaching to a ~~first-substrate~~frame having an opening a ~~second-substrate~~screen plate having a plurality of penetrating holes arranged to form a mask pattern such that the penetrating holes are positioned within the opening, the penetrating holes set to be tapered;
forming a groove on at least one of a surface of the ~~first-substrate~~frame facing the ~~second-substrate~~screen plate and a surface of the ~~second-substrate~~screen plate facing the ~~first-substrate~~frame; and
utilizing the groove to form a flow path between the ~~first-and-second~~substratesframe and the screen plate.

23. (Original) The manufacturing method of the mask as defined in claim 22, wherein at least part of the groove is formed around the opening.

24. (Currently Amended) The manufacturing method of the mask as defined in claim 22, wherein the ~~first-and-second-substrate~~frame and the screen plate are joined by anode coupling.

25. (Currently Amended) The manufacturing method of the mask as defined in claim 23, wherein the ~~first-and-second-substrate~~frame and the screen plate are joined by anode coupling.

26. (Currently Amended) The manufacturing method of the mask as defined in claim 22, wherein the steps of forming the ~~second-substrate~~screen plate includes:

forming the penetrating holes in a silicon wafer; and

cutting the silicon wafer into a shape corresponding to the ~~second~~
~~substrate~~screen plate.

27. (Currently Amended) The manufacturing method of the mask as defined in claim 22, further comprising:

forming a magnetic film over the ~~second~~~~substrate~~screen plate.

28. (Currently Amended) The manufacturing method of the mask as defined in claim 22, wherein:

a plurality of the ~~second~~~~substrate~~screen plates are attached to the ~~first~~
~~substrate~~frame;

the ~~first~~~~substrate~~frame has a plurality of the openings; and

each of the ~~second~~~~substrate~~screen plates is attached to corresponding one of the openings.

29. (Currently Amended) The manufacturing method of the mask as defined in claim 28, further comprising:

polishing surfaces of the ~~second~~~~substrate~~screen plates attached to the ~~first~~
~~substrate~~frame to have a uniform height.

30. (Currently Amended) A mask comprising:

a ~~first~~~~substrate~~frame having an opening; and

a ~~second~~~~substrate~~screen plate attached to the ~~first~~~~substrate~~frame and having a plurality of penetrating holes arranged to form a mask pattern, the penetrating holes set to be tapered, wherein:

the ~~second~~~~substrate~~screen plate is attached to the ~~first~~~~substrate~~frame such that the penetrating holes are positioned within the opening;

a groove is formed on at least one of a surface of the ~~first-substrate~~frame facing the ~~second-substrate~~screen plate and a surface of the ~~second-substrate~~screen plate facing the ~~first-substrate~~frame; and

the groove is utilized to form a flow path between the ~~first-and-second~~
~~substrates~~frame and the screen plate.

31. (Original) The mask as defined in claim 30, wherein at least part of the groove is formed around the opening.

32. (Currently Amended) The mask as defined in claim 30, wherein the ~~first-and~~
~~second-substrate~~frame and the screen plate are joined by anode coupling.

33. (Currently Amended) The mask as defined in claim 31, wherein the ~~first-and~~
~~second-substrate~~frame and the screen plate are joined by anode coupling.

34. (Currently Amended) The mask as defined in claim 30, wherein a magnetic film is formed over the ~~second-substrate~~screen plate.

35. (Currently Amended) The mask as defined in claim 30, wherein:
a plurality of the openings are formed in the ~~first-substrate~~frame;
a plurality of the ~~second-substrate~~screen plates are attached to the ~~first~~
~~substrate~~frame; and
each of the ~~second-substrate~~screen plates is attached to corresponding one of the openings.

36. (Currently Amended) The mask as defined in claim 35, wherein surfaces of the ~~second-substrate~~screen plates attached to the ~~first-substrate~~frame are polished to have a uniform height.

37. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 30; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

38. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 31; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

39. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 32; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

40. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 33; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

41. (Original) An electro-luminescence device manufactured by the method as defined in claim 37.

42. (Original) An electronic instrument having the electro-luminescence device as defined in claim 41.